

Title (en)

Process for the preparation of silver halide emulsion.

Title (de)

Verfahren zur Herstellung von Silberhalogenidemulsion.

Title (fr)

Procédé de préparation d'émulsion d'halogénure d'argent.

Publication

EP 0670515 A3 19960724 (EN)

Application

EP 95102622 A 19950223

Priority

JP 4799194 A 19940223

Abstract (en)

[origin: EP0670515A2] A process for the preparation of a silver halide emulsion comprising silver halide grains dispersed in a dispersing medium. The process comprises the steps of (1) forming host silver halide nuclei in the dispersing medium, (2) adding a halide solution to the silver halide nuclei to form a crystal defect which gives rise the formation of tabular grain, by forming at least one gap interface of halide composition in the nuclei by a halogen conversion reaction and (3) growing silver halide grains preferentially along the direction of edges of the grains to form tabular grains having an aspect ratio (diameter per thickness) of not less than 1.5 and {100} major faces. A difference in chloride content or bromide content between the halide composition of the host silver halide nuclei and the halide composition of the halide solution is in the range of 10 to 100 mol % or a difference in iodide content between the halide composition of the host silver halide nuclei and the halide composition of the halide solution is in the range of 5 to 100 mol %. <IMAGE>

IPC 1-7

G03C 1/015; G03C 1/035

IPC 8 full level

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CPC (source: EP)

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G03C 2001/03511 (2013.01); **G03C 2001/03517** (2013.01); **G03C 2001/03523** (2013.01); **G03C 2001/03535** (2013.01);
G03C 2001/03558 (2013.01); **G03C 2200/01** (2013.01)

Citation (search report)

- [Y] EP 0569971 A2 19931118 - FUJI PHOTO FILM CO LTD [JP]
- [Y] EP 0312959 A1 19890426 - FUJI PHOTO FILM CO LTD [JP]

Cited by

US5888718A; US5885762A; US5908740A; US5879874A; EP0670514A3; US5906913A; US5905022A

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